

# SEM (Inspect F)

주사전자현미경

Inspect F enables high-resolution inspection and characterization capabilities using a high brightness / high current Schottky field emission source providing clear, sharp and noise free imaging.

## Model

FEI (Inspect F)

## Specifications

- Accelerating voltage : < 30 kV
- SEM resolution : < 1.0 nm
- Magnification : 10 ~ 500,000 X
- Everhardt Thornley SED

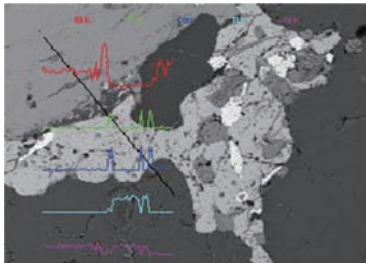
## Applications

- Electron beam current measurement
- EDS
- EBL (Electron Beam Lithography)
- EBIC (Electron Beam Induced Current)

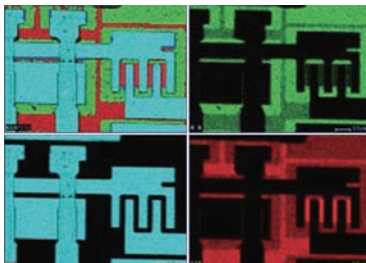


**Location** L5145 Tel.02-958-4945

### EDS mapping and line analysis

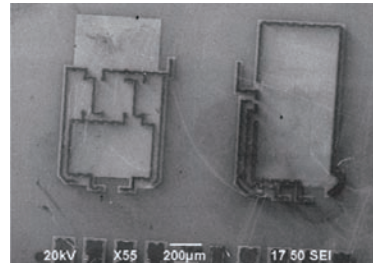


Various line-scan collect and display options

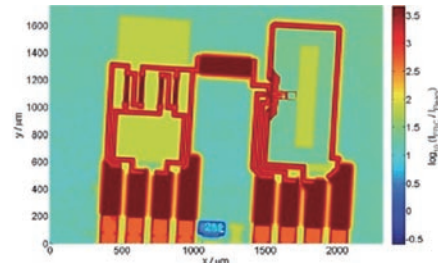


Mapping for every analytical requirement

### EBIC (Electron beam induced current)

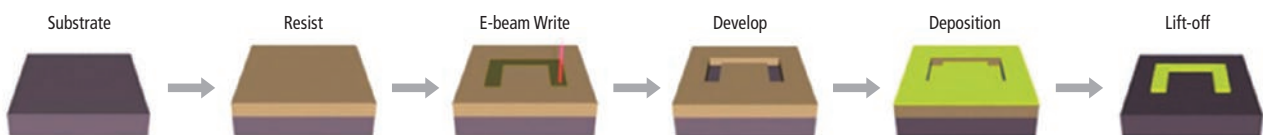


Secondary electron image of a part of a sensor circuit



The logarithm of the EBIC current signal measured

### Electron-beam lithography (EBL)



A six stage lithography process known as electron beam lithography